

# Inverse Design in Photonics

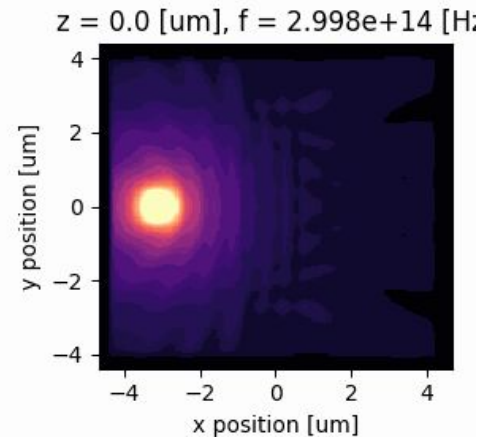
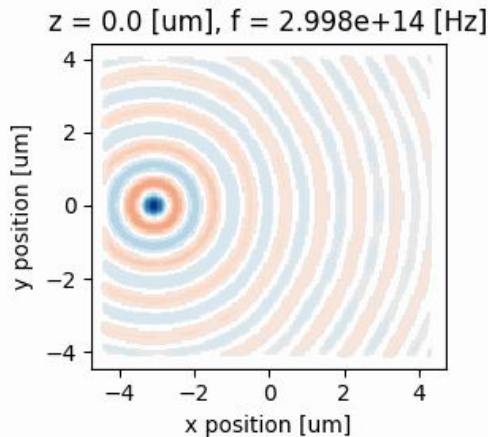
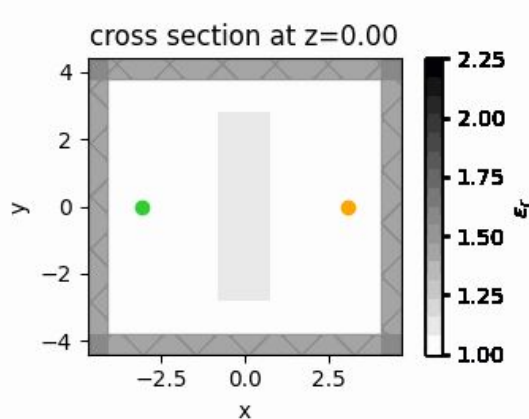
## Tutorial 4: Basic Feature Constraints





# Review: Inverse Design Process

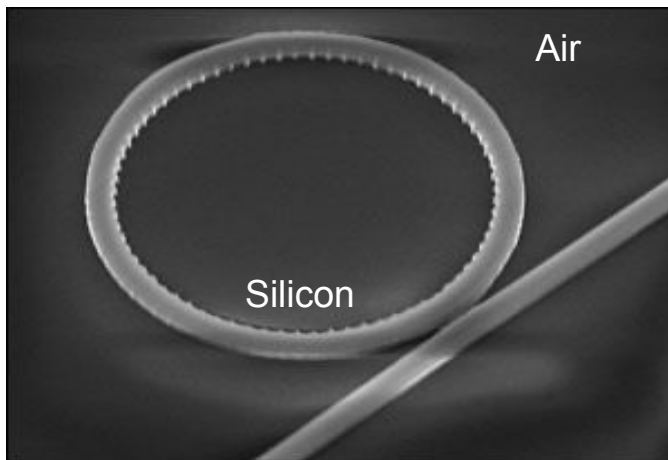
- Last time, we gave a simple demo of using inverse design to make a lens.
- This time we will discuss how to create a more realistic device satisfying fabrication constraints.





# Defining Devices

- For example: in Silicon photonics, one can define a device by etching Silicon.
- The structure can only include silicon regions and air regions.
- Typically there are constraints regarding feature size that can be etched.
- Need to take this into account in the optimization algorithm.





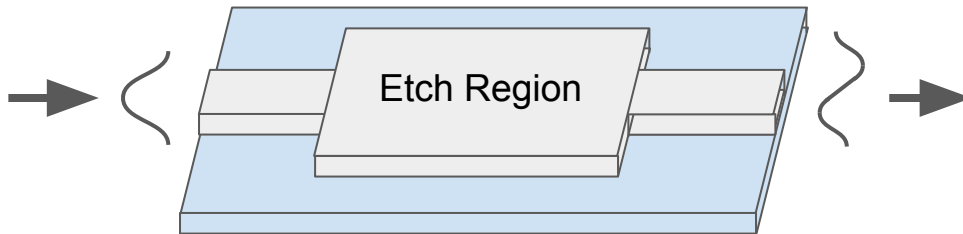
# Demo: Si Photonics Mode Converter

## System:

- Silicon waveguide on SiO<sub>2</sub> structure with waveguide inputs and outputs.
- Rectangular “design region” that can be etched to remove some of the Si.

## Goal:

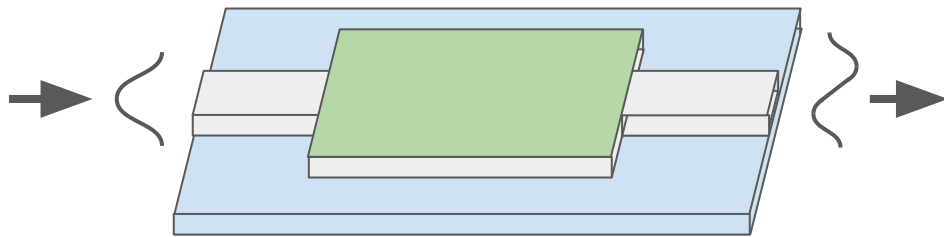
- Design the central region to convert one waveguide mode to another.
- Objective function: maximize mode overlap with desired output mode.



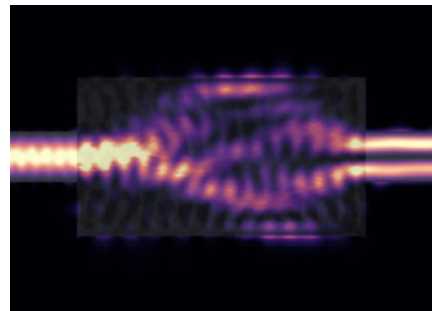


# Without Feature Size Constraints

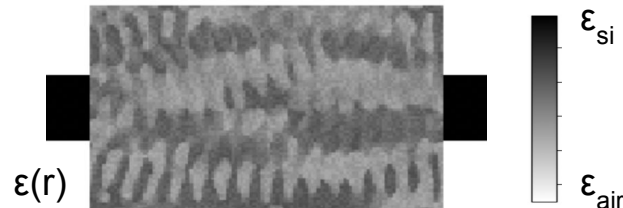
Directly optimize the dielectric function inside of the design region (green):



device works



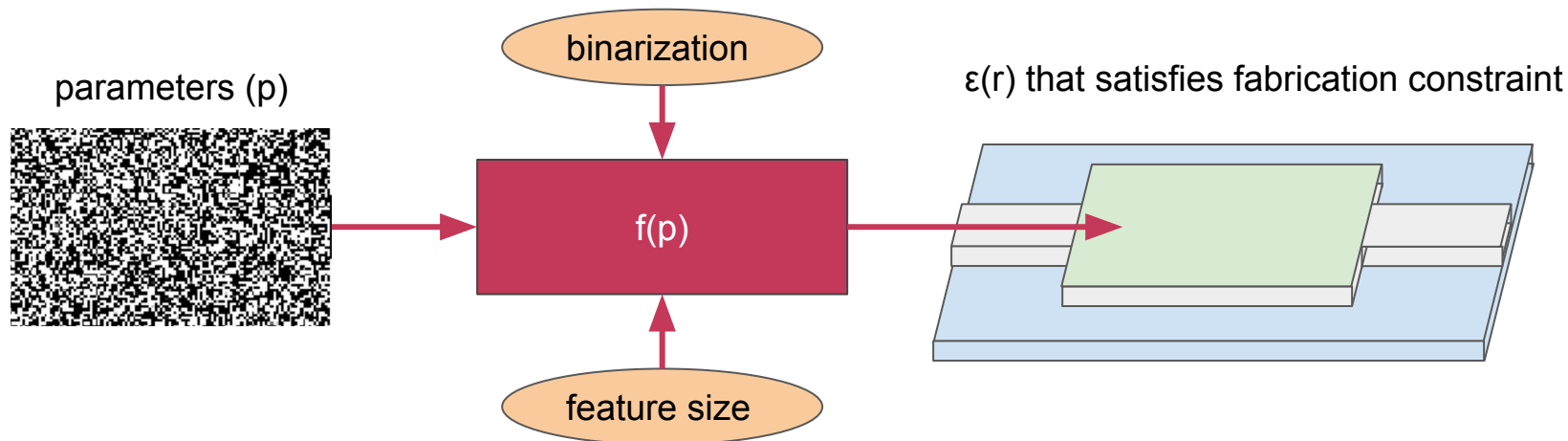
but is not binarized or fabricable





# Parameterization

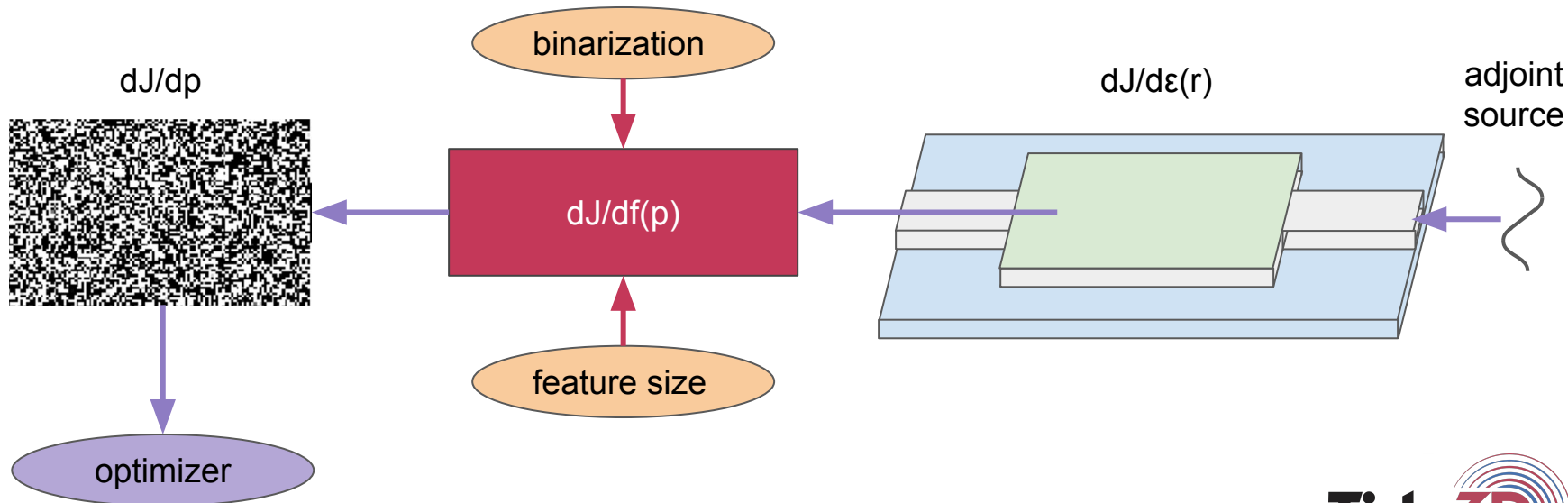
- General idea: express your dielectric function / device as a function of the parameters.
- Choose the function to express your desired fabrication constraints.





# Differentiating Parameterization

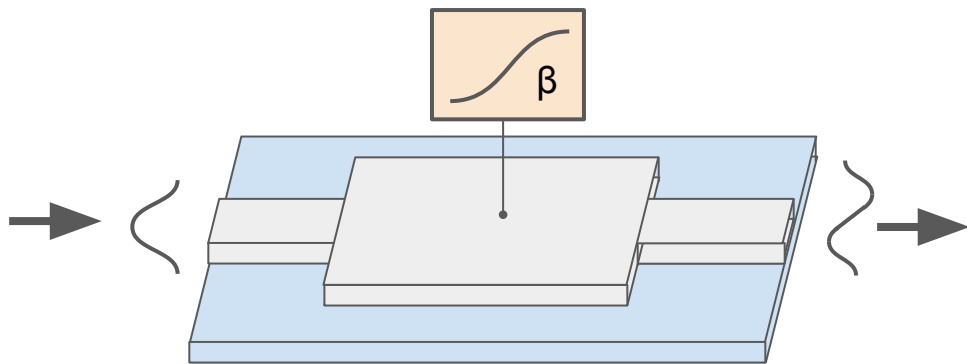
- Important to ensure smooth, differentiable parameterization.
- Use adjoint method to compute gradient (purple) through to the base parameters.



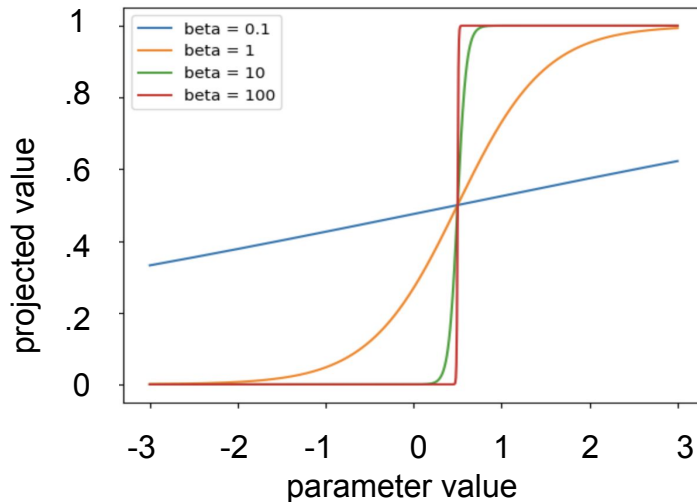


# Imposing Binarization

- Introduce a tanh projection to binarize permittivity in each pixel.
- Increase  $\beta$  to make it hard for the pixel permittivity to be in the middle.



$$\epsilon(p) = \tanh(\beta p) \frac{\epsilon_2 - \epsilon_1}{2} + \frac{\epsilon_2 + \epsilon_1}{2}$$

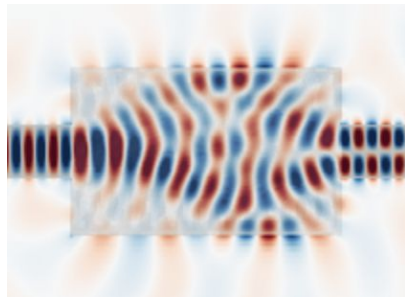
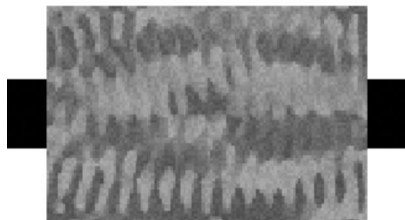






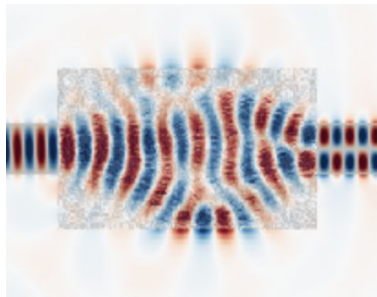
# Binarization Results

$\beta=0.1$



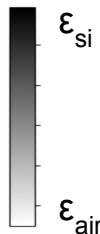
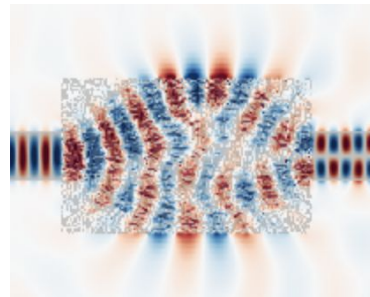
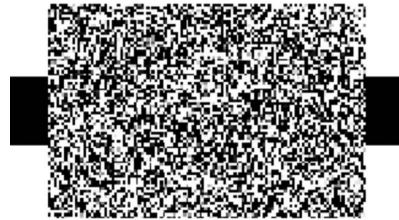
successfully converts modes

$\beta=1$



binarized, but not fabricable

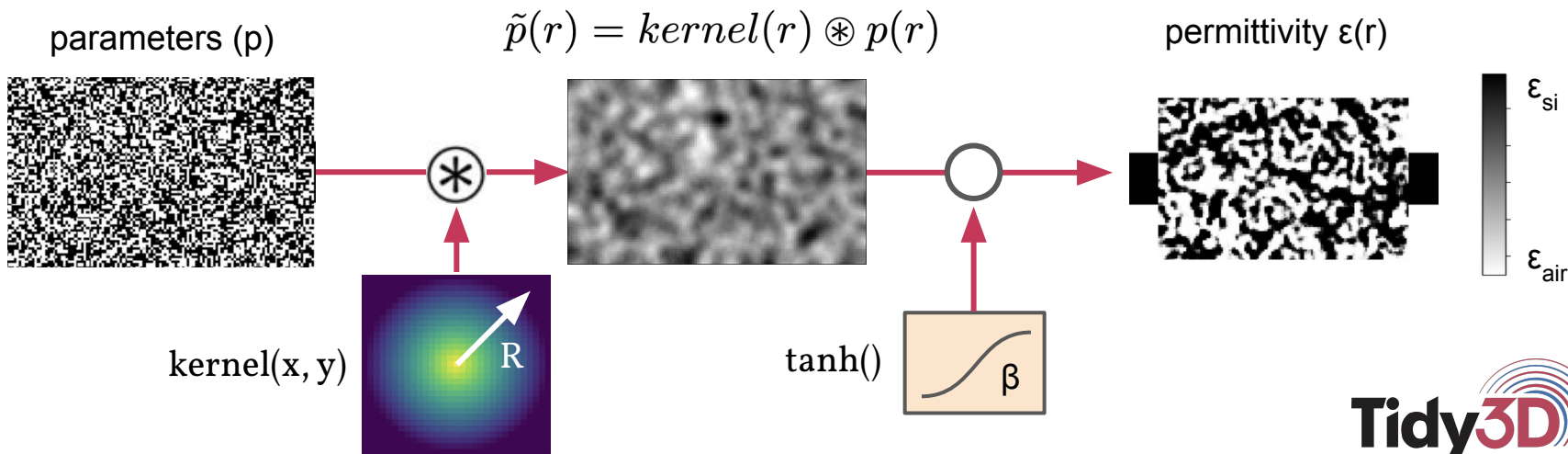
$\beta=10$





# Issue: the pixels are too small to fabricate!

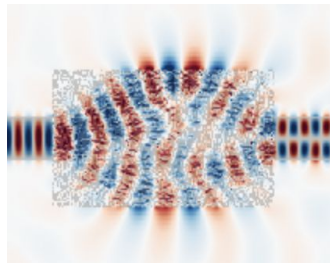
- Introduce a “filter” that smooths the influence of each pixel over a radius “R”.
- Increasing “R” enforces larger feature sizes.
- Convolve each parameter with a conic filter before tanh projection.



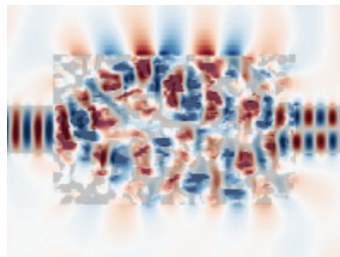


# Smoothing Results

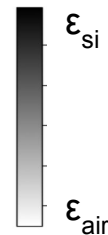
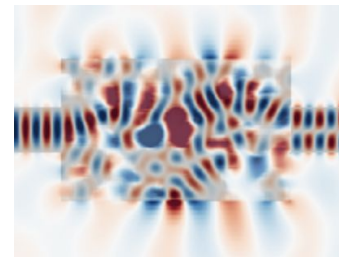
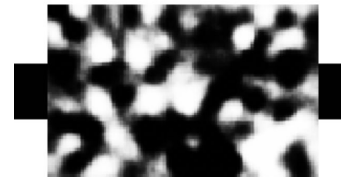
$R = 0$



$R = 100 \text{ nm}$



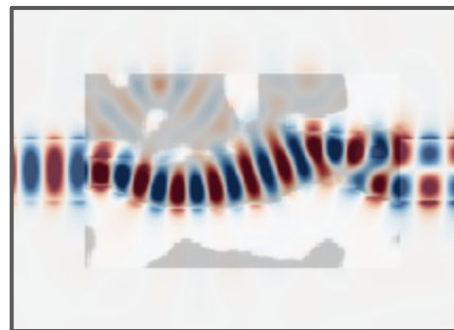
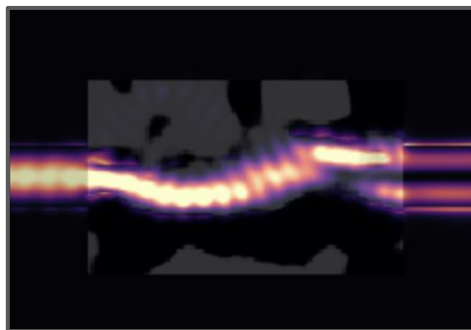
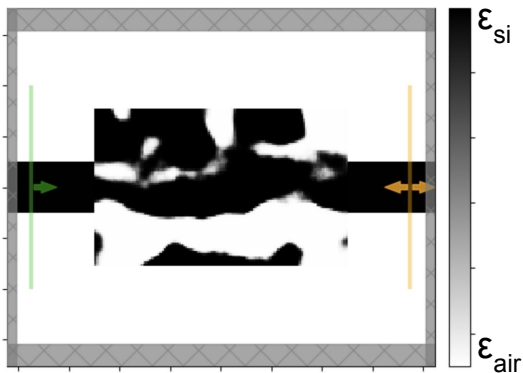
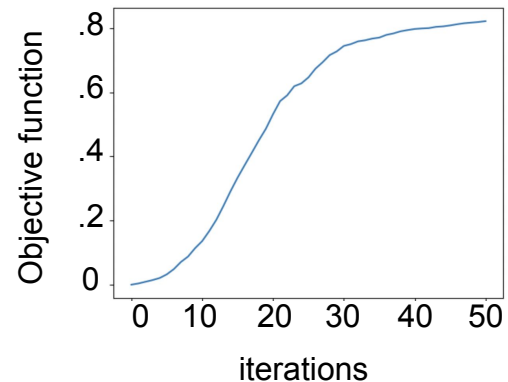
$R = 300 \text{ nm}$





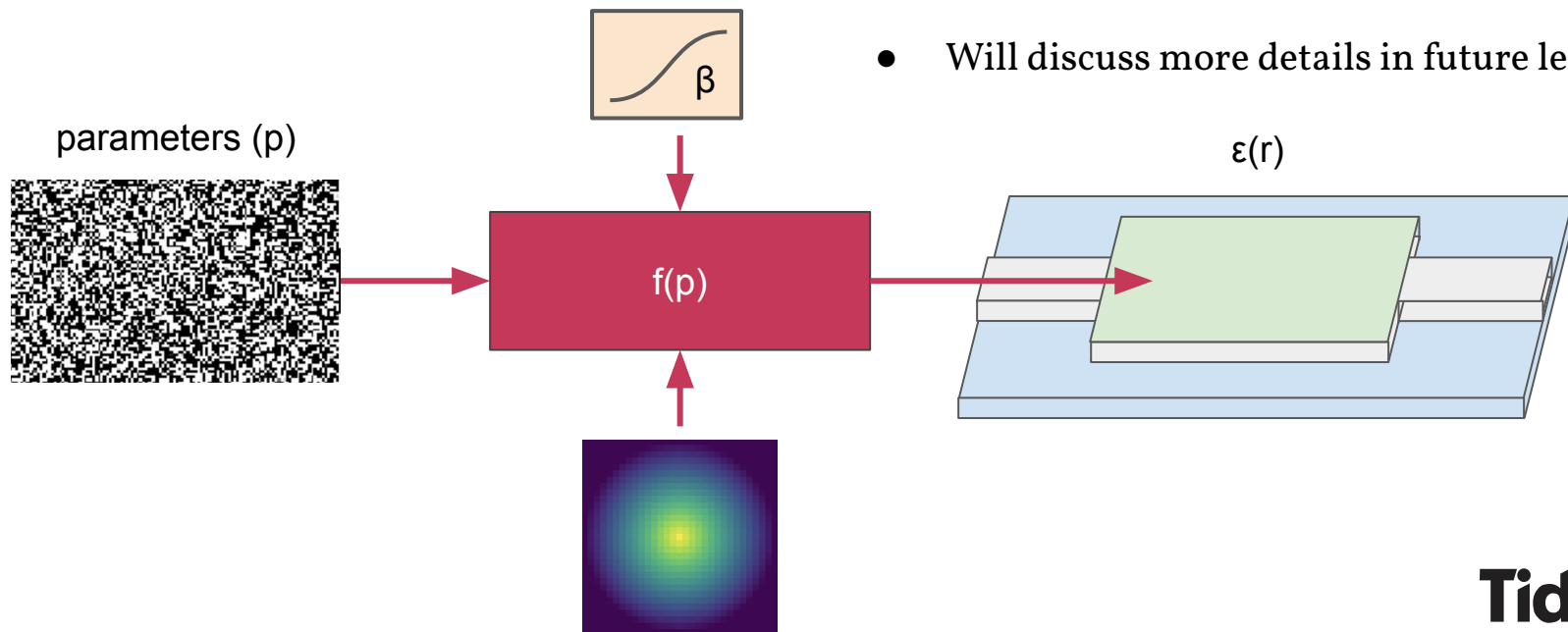
# 3D Optimization Results

- 50 iterations of optimization.
- Convolve with conic filter w/ radius=500 nm.
- Tanh projection with  $\beta=200$ .





# Takeaway



- Important to craft the parameterization that implements the feature constraints you care about.
- Will discuss more details in future lectures.